

SEMICONDUCTOR PROCESS CHAMBER AND SEMICODUCTOR PROCESS APPARATUS

ABSTRACT

The present disclosure provides a semiconductor process chamber and semiconductor process apparatus, the semiconductor process chamber includes an outer chamber with multiple reaction areas inside, each reaction area is provided with a reaction chamber, a carrying device and a sealing assembly; the bottom end of the reaction chamber has an opening; the carrying device includes a liftable support shaft and a carrier for carrying wafers, the support shaft is provided at the bottom of the carrier, is configured to support the carrier, and ascends and descends between a processing position in the reaction chamber and a transferring position below the reaction chamber through the opening; the sealing assembly is arranged below the carrier and connected to the carrying device, and the support shaft passes through the sealing assembly, the sealing assembly is configured to ascend and descend with the support shaft, and when the support shaft supports the carrier to ascend to the processing position, it contacts the bottom end of the reaction chamber to seal the opening. The semiconductor process chamber and semiconductor process apparatus provided by the present disclosure may improve the sealing stability of the sealing assembly and may improve the stability of the semiconductor process chamber and semiconductor process apparatus in use.

FIGURE 1